Aberration Corrected Wien Filter as a Monochromator of High Spatial and High Energy Resolution Electron Microscopes

K. Tsuno*, D. Ioanoviciu** and G. Martinez***

- * JEOL Ltd., 1-2, Musashino 3-chome, Akishima, Tokyo 196-0001, Japan
- ** Institute of Isotopic and Molecular Technology, P.O. Box 700, R-3400, Cluj-Napoca, Rumania
- *** Dept. Fisica Aplicada III, Facide Fisica, Univ. Complutense, E-28040, Madrid, Spain

Monochromator inside a field emission gun (FEG) is an essential tool in high spatial and high energy resolution analytical electron microscopy. Wien filter has a straight optical axis and suitable as a gun monochromator. One of the authors designed a double Wien filter monochromator for Tanaka [1]. Although the size of virtual crossover size of FEG is about a few tenth nanometers, it increases to about a micron after passing through the monochromator. Monochromator reduces the current of the beam about 1/10 by the selection of the energy by the slit. If the beam must be reduced by the condenser lens system, the beam current must be lost further. The origin of the large beam size is the aberrations.

We have made an accurate numerical simulation using BEM [4] and found that 12-pole filter can give almost zero hexapole field components including the fringing region. If we have no special field distributions around the fringing region, it is possible to analyze aberrations analytically considering both of objective and image points inside the fields. We have made an analytical theory of Wien filter up to 3rd order. Because the equations of the third order aberration are so long and not possible to write in this short abstract. We will show only the computed results.

FIG. 1 shows electron ray trajectory of a double Wien filter under the stigmatic focus condition for two beams with 1000V (blue and solid beams) and 990V (red and broken beams) for dispersion direction (X; upper figure) and perpendicular direction (Y; lower figure). The beam incidence half angle is 50 mrad, which is extremely large compared to the actual machine, but selected to show the aberration figure of the beam. The beam shows a large aberration at the middle (region with the triangular shape at the middle of the filter), where the slit for selecting the beam energy is inserted. However, at the image plane (right end of the trajectory), aberration vanishes.

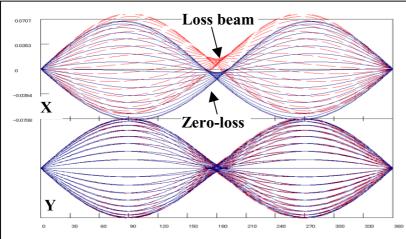


FIG.1. Electron rays of stigmatic focus Wien filter for X- and Y-axes.

FIG. 2 shows aberration figures on the slit plane, where the zero loss (left figures) and loss beams (middle figures) are separated, and on the image plane (right figures), where the both beams are concentrated to form an achromatic image. Conditions of the fields are: $e_2 =$ - (m+2) / 8, $b_2 = m / 8$ and $(e_3-b_3) = m / 16$ for m=0~6. The condition m=0 is the stigmatic focus condition it with FIG. 1 and m=6 is Rose's condition [2].

Rose's condition gives a small beam on the slit plane, and gives a large energy resolution. Here, we propose a new condition, m=2, where the geometrical aberration on the image plane is completely vanish up to the third order. Negative chromatic aberration is left on the image plane. At this plane, all the conditions m=0 to 6 give zero geometrical aberrations (that means aberration figure is a point) up to the 2nd order. However, if we consider aberrations up to the 3rd order, all the geometrical aberrations disappear only when m=2.

References

- [1]. M. Tanaka et al., Microsc. Microanal. 8 (Suppl. 2) 68.
- [2]. H. Rose, Optik **34** (1987) 26.
- [3]. K. Tsuno and J. Rouse, J. Electron Microsc. 45 (1996) 417. [4]. G. Martinez and K. Tsuno, Ultramicroscopy 93 (2002) 253.
- Stigmatic condition m=0m=1Present new proposal m=2Zero loss m=4Zero loss Loss beam Loss beam m=6 Rose's proposal

FIG.2. Aberration figures on the slit and image planes.